AIChE JOURNAL

VOL.49, NO.9 SEPTEMBER 2003

The AIChE JOURNAL, a monthly publication of the American Institute of Chemical Engineers, is devoted to fundamental research and developments having immediate or potential value in chemical engineering.



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Group Publisher Stephen R. Smith AIChE Journal (ISSN 0001-1541) is published monthly by the American Institute of Chemical Engineers, Three Park Avenue
New York, NY 10016-5991.

Manuscripts should be submitted to the AIChE Journal Editorial Office Dept. of Chemical Engineering University of Delaware Newark, DE 19716-3110 Tel 302.831.6858 Fax 302.831.3226. E-mail: aichei@che.udel.edu

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